

LASER-PRODUCED ELECTRON BEAMS IN MATTER

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1: "normal" compression with ns laser beams

▶ 2: a CPA laser creates a beam of relativistic electrons (lateral hot spot)



Study of fast electron propagation is essential and it turns out that it could be inhibited by self generated electric fields. Bell's model

 $z_{o} (\mu m) = 3 \ 10^{-3} \ \sigma (10^{6} (\Omega m)^{-1}) \ T^{2}_{fast} (keV) / \eta \ I_{L} (10^{17} \ W/cm^{2})$

 $\sigma \text{ ELECTRICAL CONDUCTIVITY OF BACKGROUND MATERIAL}$





- Study of the transport in matter of intense electron beams produced by high intensity laser pulses
- Kα images on x-ray CCD studied as a function of target material (insulators vs. conductors) and target thickness
- Set of "updated" diagnostics:
 - Kα x-ray CCD
 - Shadography (2ω)
 - RCF film stack for proton emission
 - Pin Hole Camera (PHC) for X-ray emission



Xtream Light-III



Chinese Academy of Sciences, Beijing



15 J / 50 fs / 20 min, 350TW

Ti: sapphire $\lambda = 800 \text{ nm}$









DOUBLE LAYER TARGETS:

Propagation layer:



\bigstar Copper 0 - 40 μ m (i.e. pure Cu targets)

10 μm Cu tracer layer (no good signal with thinner Cu)









Spherically bent quartz crystal 211 2d = 3.082 Å; \emptyset = 3 cm R = 380 mm; Magnification \approx 4



Pre-pulse problem



1 to 3 % of laser energy was contained in a prepulse







Shadowgraphy images







25 μm Cu, 0 ps, 4.2 J 25 μm Cu, 250 ps, 4.35 J 25 μm Cu, +100 ps, 3.4 J

Targets 25 μ m Cu are not drilled through





Typical fast electron energy

The energy of fast electrons is $\approx 150 \text{ keV}$ using the scaling law by Beg et al. [Phys. Plasmas, **4**, 447 (1997)]

 $T_{hot} \approx 100 \text{ keV} (I \lambda^2)^{1/3}$

 λ in μm ; I in units of 10^{17} W/cm^2









Collisional Penetration Ranges for 150 keV

- **Cu** 0.043 g/cm² --> exp 0.014 g/cm²
- Al 0.037 g/cm² --> exp 0.0075 g/cm²
- **CH** 0.026 g/cm² --> exp 0.005 g/cm²

(<u>http://physics.nist.gov/PhysRefData/Star/Text/con</u> <u>tents.html</u>)

What is the origin of the difference? (a factor \approx 3-5)





 $z_{o} (\mu m) = 3 \ 10^{-3} (kT_{fast})^2 \sigma_6 / I_{17}$

 σ = 59.6 $\,10^6$ for Cu and 37.8 $\,10^6$ for Al

We find large numbers (800 μ m or 0.2 g/cm² for Al)

No Electrical Inhibition?

And what about plastics?











The value $z_o = 0.2 \text{ g/cm}^2$ for cold Al ($\sigma = 37.8 \text{ 10}^6 (\Omega \text{ m})^{-1}$) implies that we get the experimental value 0.0075 g/cm² for $\sigma \approx 1.4 \text{ 10}^6$ or a temperature T $\approx 5 \text{eV}$.

At the same temperature $\sigma \approx 2 \ 10^5 \ (\Omega \ m)^{-1}$ for CH giving $z_o = 0.001 \ g/cm^2$ in the same range of experimental data (0.005 g/cm²) while collisional penetration was 0.026 g/cm²





The K α spot size diminishes as target thickness increases



Effect of self-pinching due to magnetic fields?



propagation layer

target rear side

laser beam

Fast electrons are produced with an angular distribution $g(\Theta)$ and an energy distribution f(E).

The smaller the energy, the larger the angle (??)

For small thickness, we observe the effect of large Θ , as thickness is increased we see the effect of larger energies (lower energies electrons have been already stopped) and smaller Θ .

Our data clearer: K α spot diminishes instead of remaining constant







Cu 35 μm E = 4.7 J







J. A. Koch, et al. "Experimental measurements of deep directional columnar heating by laser generated relativistic electrons at nearsolid density" Phys. Rev. E 65, 016410 (2001)

FIG. 1. X-ray pinhole images of thin diagnostic layers buried in CH targets. (a) is from an Al layer, buried 15 μ m under the front surface and (b) from a Au layer at a depth of 50 μ m. (c) is from a Au layer at a depth of 100 μ m, viewed from the back of the foil. In contrast, (d) shows the solid spot emitted by a solid Au film viewed from the front.



Figure 2. A 50TW laser pulse on a 175µm thick mylar target, corresponding to an intensity of 2×10¹⁹ Wcm⁻² within the focal spot. The heated plasma on the rear surface of the target exhibits a central heated region surrounded by an annular structure with a total divergence angle of 20°.

P. A. Norreys, et al. "Observation of annular electron beam transport in multi-TeraWatt laser-solid interactions" Plasma Phys. Control. Fusion, 48, N. 2 (February 2006)





First experiment realized with the new XL-III 350 TW fs laser facility Academy of Sciences Beijing China

- Prepulse problem \Rightarrow low fast electron energy
- No match with collisional predictions
- Significant electric inhibition, background temperature ≈ 5 eV
- Spot size decreases with thickness (effect of angular/energy distribution?)
- Annular propagation at large distances. Role of self generated magnetic fields?

Clear experimental data show effects previously observed only at higher laser intensity







Thank you !!



We are looking for information about:

- Penetretion range
- Fast electron beam geometry



Our results in agreement with Key et al. [Phys.Plasmas, 5, 1966 (1998)]. At larger laser intensity and fast electron energy 640 keV, they got:

 $0.032 \text{ g/cm}^2 \text{ for CH} \Rightarrow 320 \text{ microns}$ $0.1 \text{ g/cm}^2 \text{ for Al} \Rightarrow 370 \text{ microns}$ $0.195 \text{ g/cm}^2 \text{ for Cu} \Rightarrow 220 \text{ microns}$





Collisional stopping power in the non-relativistic regime

$$\frac{dE}{dx} = \frac{K}{\rho m v^2} \ln(..) \implies x \propto E^2$$

Electrical Penetration Range (Bell's law)

$$z_o = 3 \ 10^{-3} \ (kT_{fast})^2 \sigma_6 \ I_{17}^{-1} \ \mu m$$

Now

$$\left(\frac{150 \ keV}{640 \ keV}\right)^2 = 0.055$$

320 μ m for CH \Rightarrow 18 μ m (measured 50 μ m) 370 μ m for Al \Rightarrow 20 μ m (measured 28 μ m) 220 μ m for Cu \Rightarrow 12 μ m (measured 16 μ m)

Agreement is fair (we have large error bars)



Self-generated magnetic-field effect?





Fast electron number density given by LSP 800 fs after the fast electron beam was injected at the target front surface for an intensity of 6 10¹⁹ W/cm².